

Characterizing MoS₂-Si p-n Heterojunction Using Laser Terahertz Emission Spectroscopy

Rebecca Wong,^{1,2,3} F.R. Bagsican,³ I. Kawayama,³ M. Tonouchi,³ B. Li,⁴ R. Vajtai,⁴ P. Ajayan,⁴ and J. Kono^{2,4}

¹ Department of Physics, Grinnell College

² Department of Electrical and Computer Engineering and NanoJapan Program, Rice University

³ Institute of Laser Engineering, Osaka University, Japan

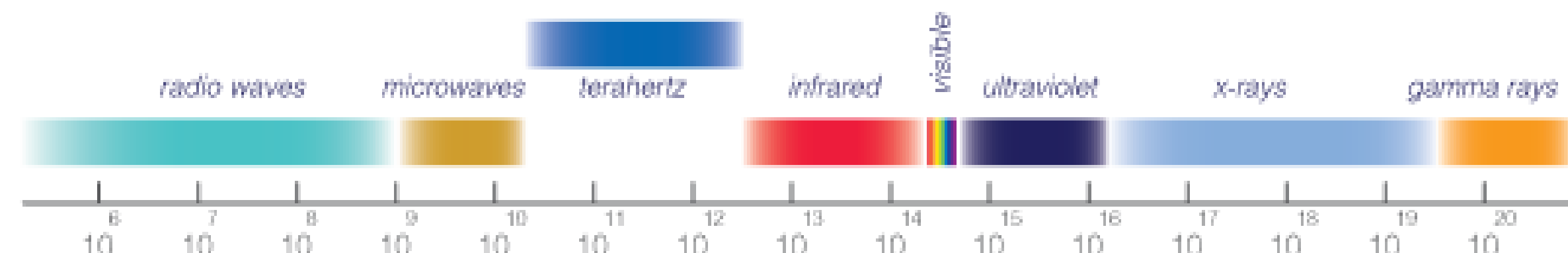
⁴ Department of Materials Science and NanoEngineering, Rice University



Introduction

The “Terahertz Gap”

- Spectral region 0.3 – 3.0 THz (1 mm - 100 μ m)



- Final frontier for improving optoelectronic and electronic devices
 - Low energy usage

Atomically thin two-dimensional (monolayer/2D) materials differ significantly from bulk (3D) counterparts

- Van der Waals bonds (2D) vs. covalent bonds (3D)
- MoS₂ characteristics
 - Direct band gap of 1.8 eV (2D) vs. indirect band gap of 1.3 eV (3D)
 - Stable charge exciton state at room temperature (2D)
- Unique applications for optoelectronic and electronic devices

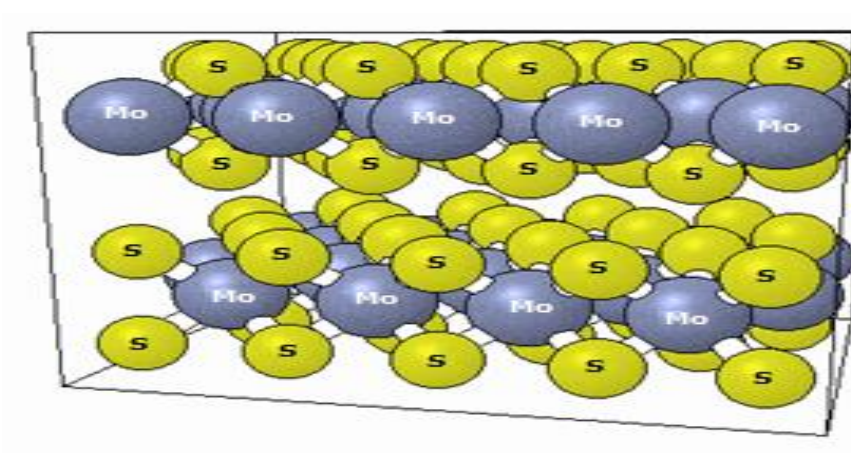


Fig. 1: Atomic structure of MoS₂



Fig. 2: Bulk MoS₂ sample



Fig. 3: Monolayer MoS₂ sample

Objectives

Investigate 2D-3D heterojunction MoS₂-Si

- n-type (electron majority carrier) monolayer MoS₂ and p-type (hole majority carrier) bulk Si

Gain new insight into the nature of the MoS₂-Si p-n junction energy states

- Band alignment
- Band bending

Understand how the properties of 2D-3D junctions differ from those of conventional 3D-3D junctions

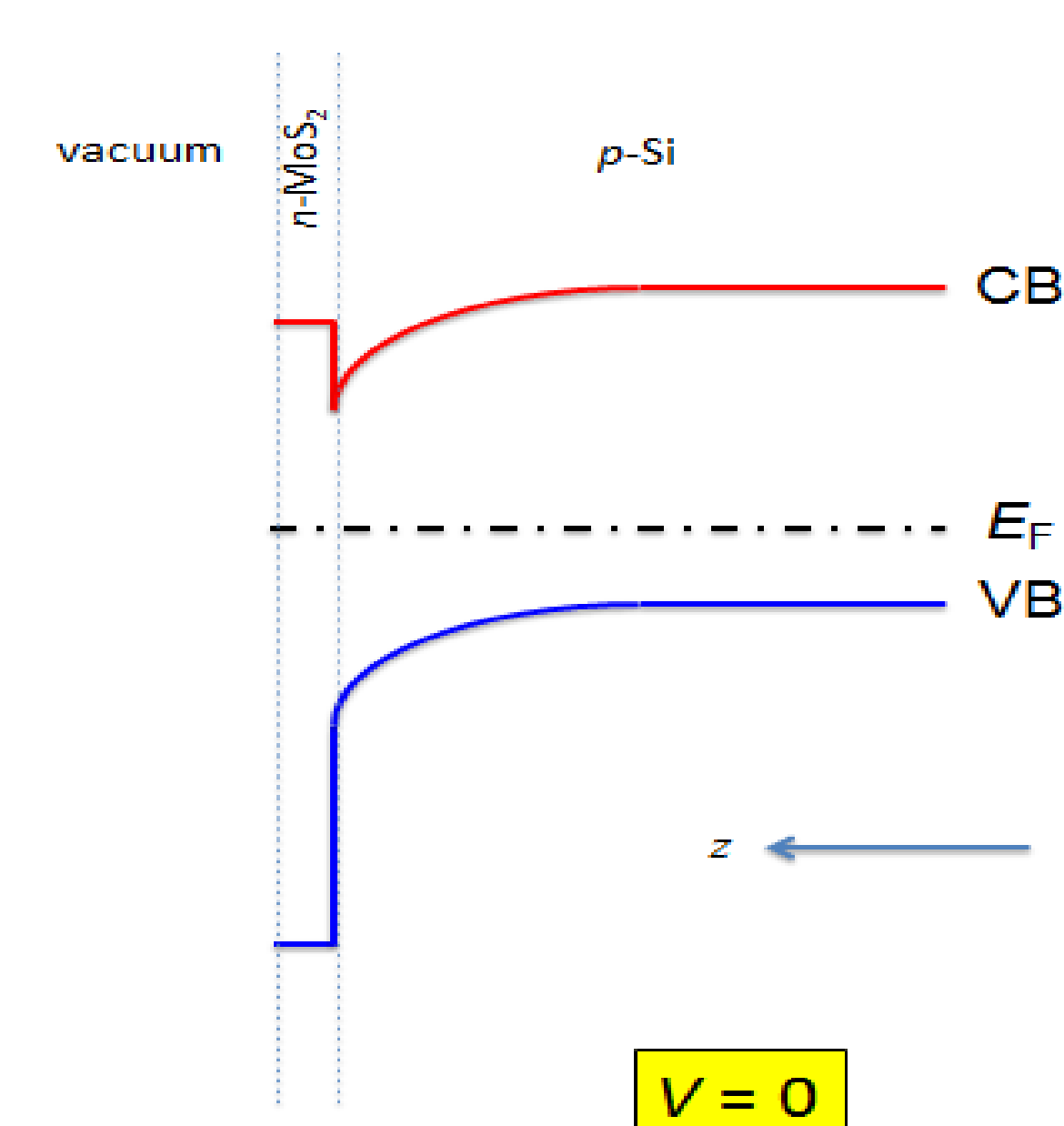


Fig. 4: Band diagram of MoS₂-Si heterojunction¹

Methodology

Laser Terahertz Emission Spectroscopy and Imaging

- Sensitive to electric fields in MoS₂-Si heterojunction
 - Map out distribution of electric fields (band bending)

Optical Imaging

- Determine resolution of system
- Optimize alignment of system in order to perform terahertz imaging

Methodology

Terahertz Imaging

- Determine if there is terahertz emission from MoS₂ p-n heterojunction

Raman Microscopy and Spectroscopy

- Monitor the deterioration of MoS₂ p-n heterojunction and categorize different materials within the sample

Framework

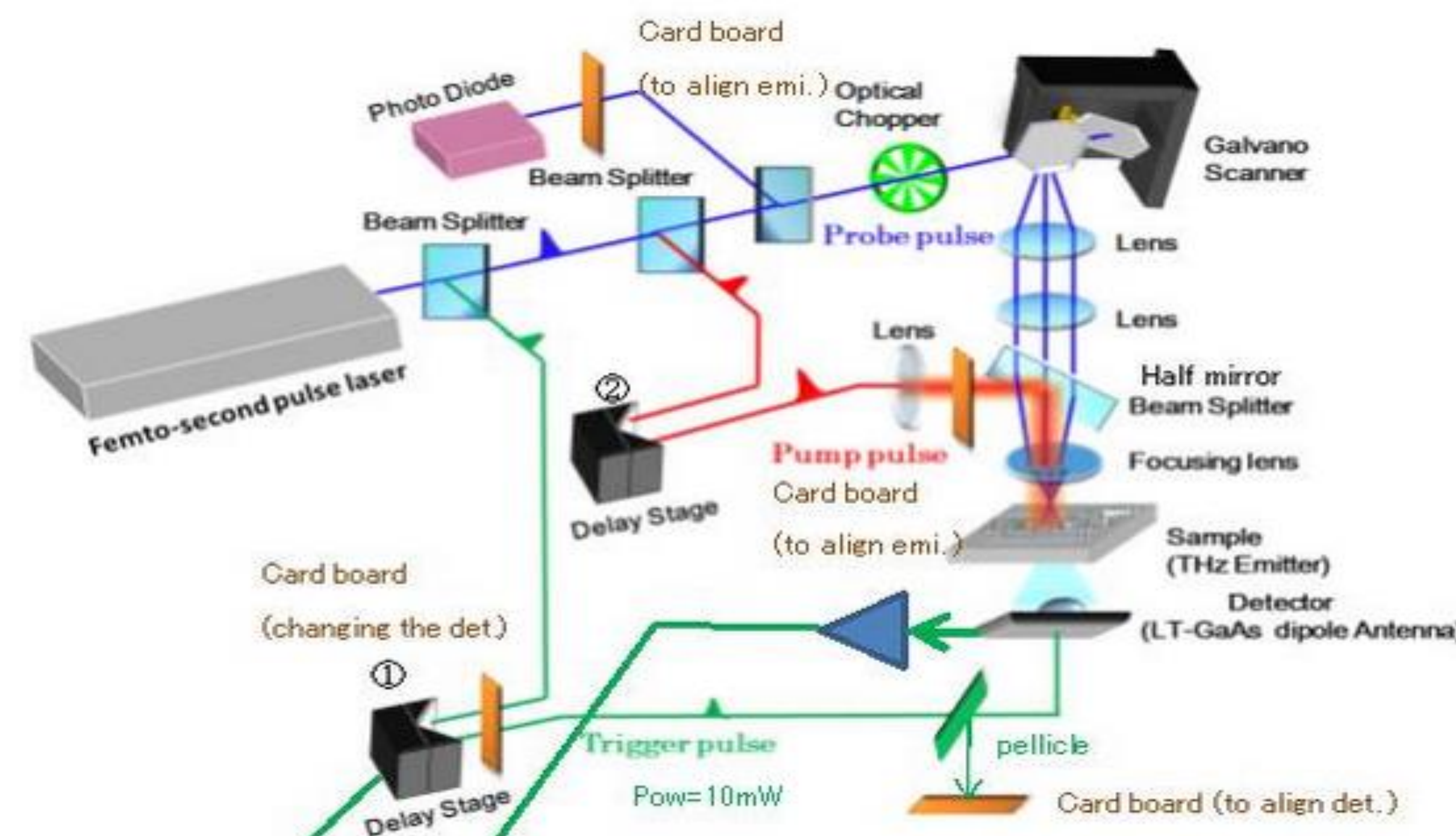


Fig. 5: Schematic of terahertz system setup

Results and Discussion

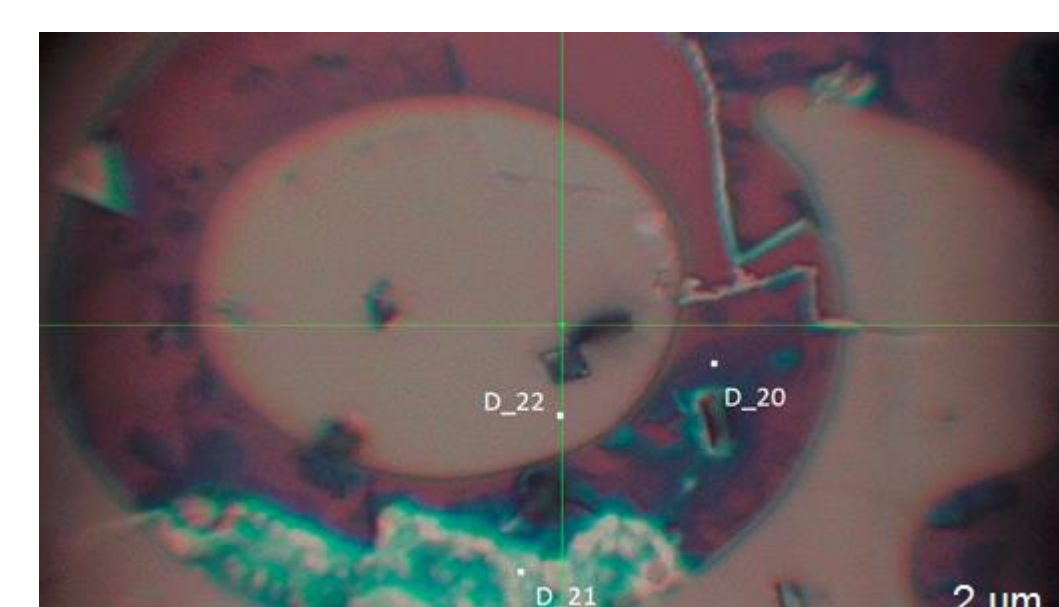
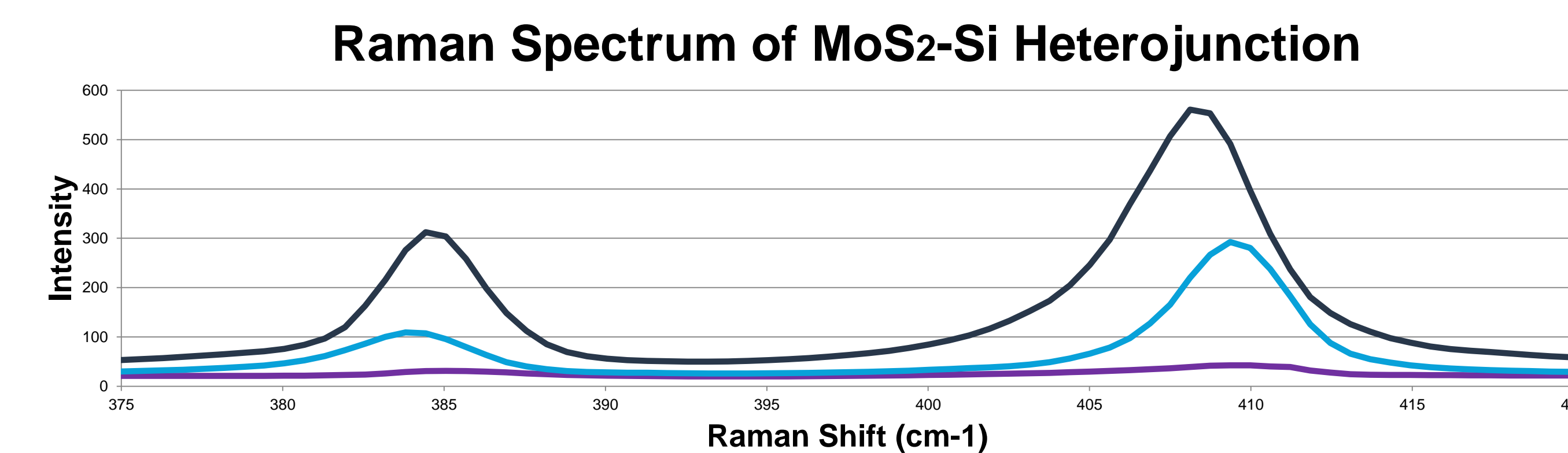
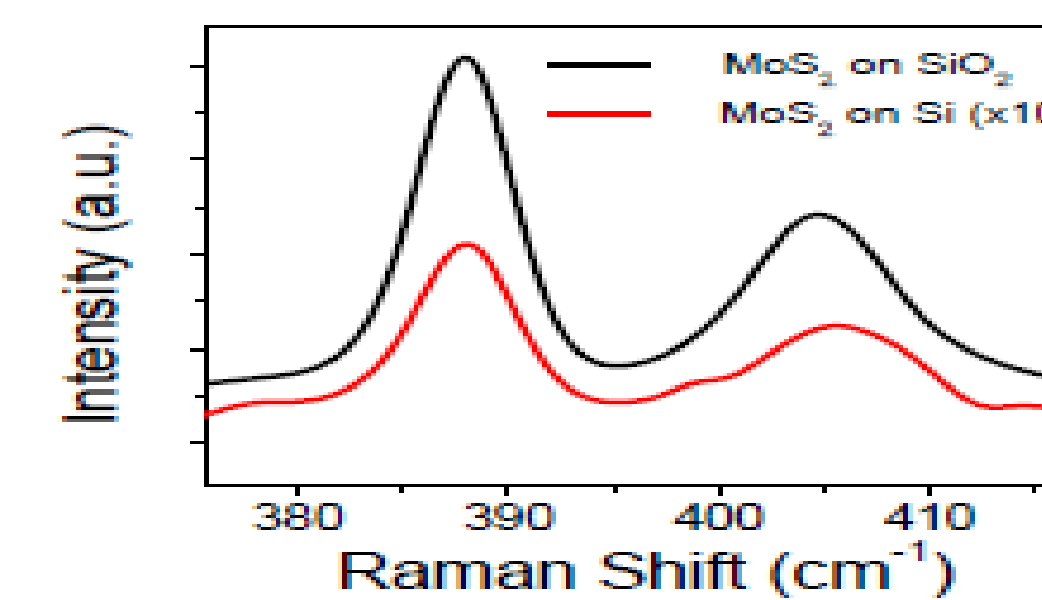


Fig. 6 (left): Raman spectroscopy sampling areas of MoS₂-Si with PMMA removed

Fig. 7 (right): Previously found Raman peaks of MoS₂ on silicon and silicon dioxide¹



D₂₀ and D₂₁ have Raman peaks characteristic of monolayer and bulk MoS₂ respectively

D₂₂ has Raman peaks characteristic of silicon only

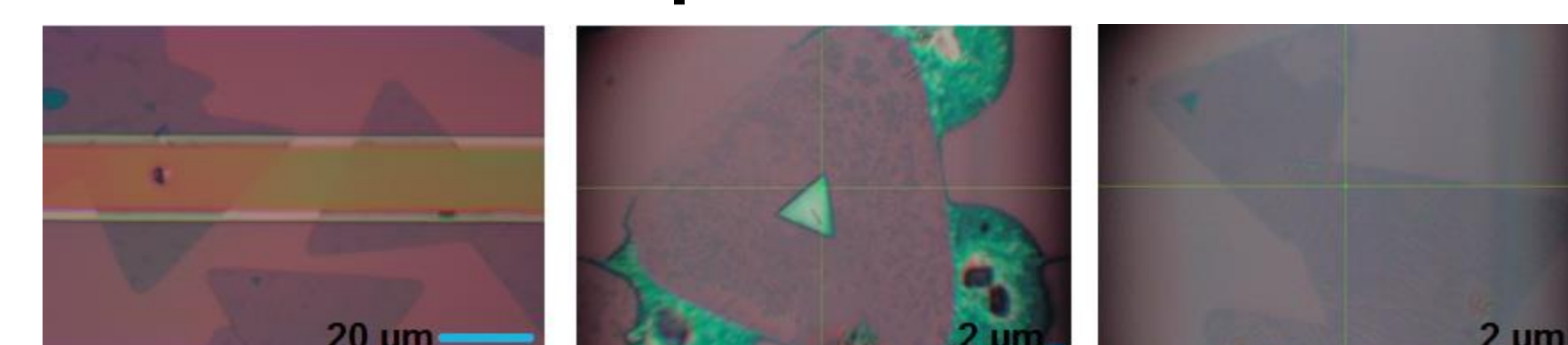


Fig. 8: Furthestmost left image is of the sample freshly prepared. The other two images are of the sample one month later. All images are magnification X100. The furthestmost right two images were acquired using Horiba XploRA ONE Raman microscope.

Results and Discussion

Current alignment and resolution of system

- Photoconductive antenna

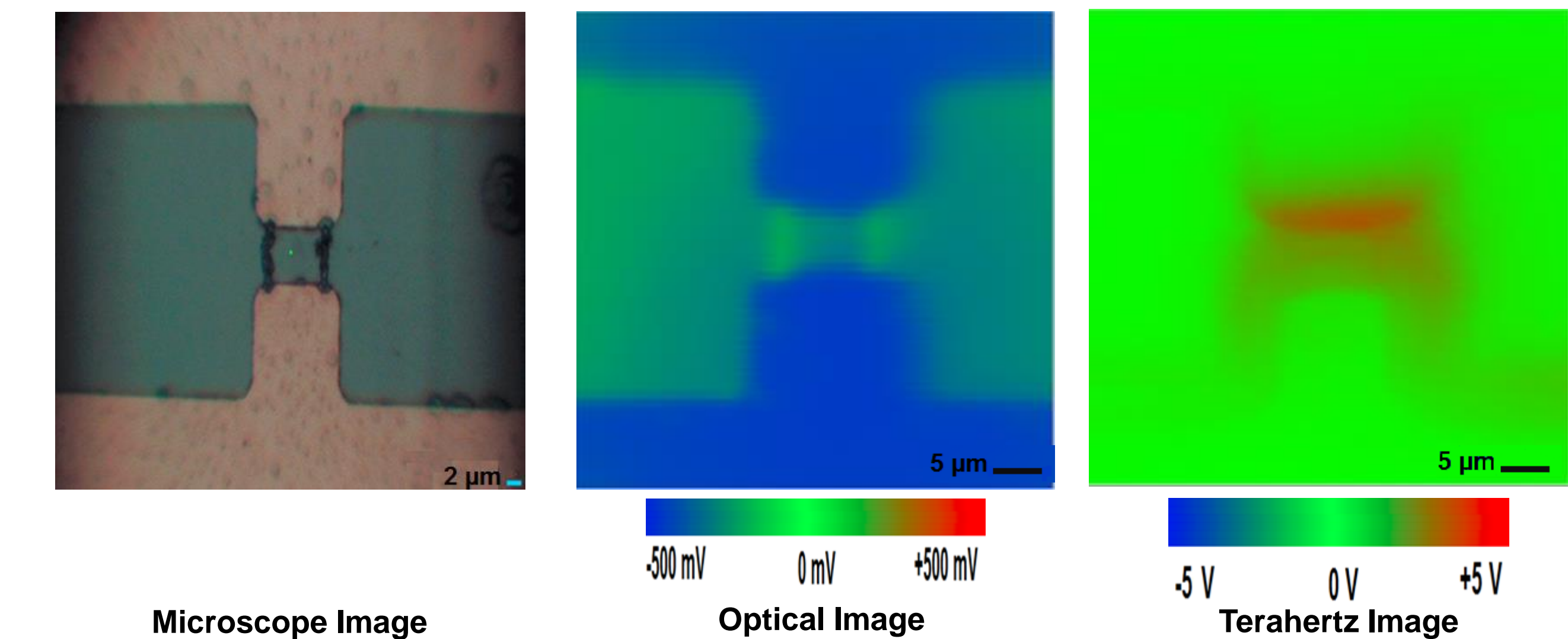
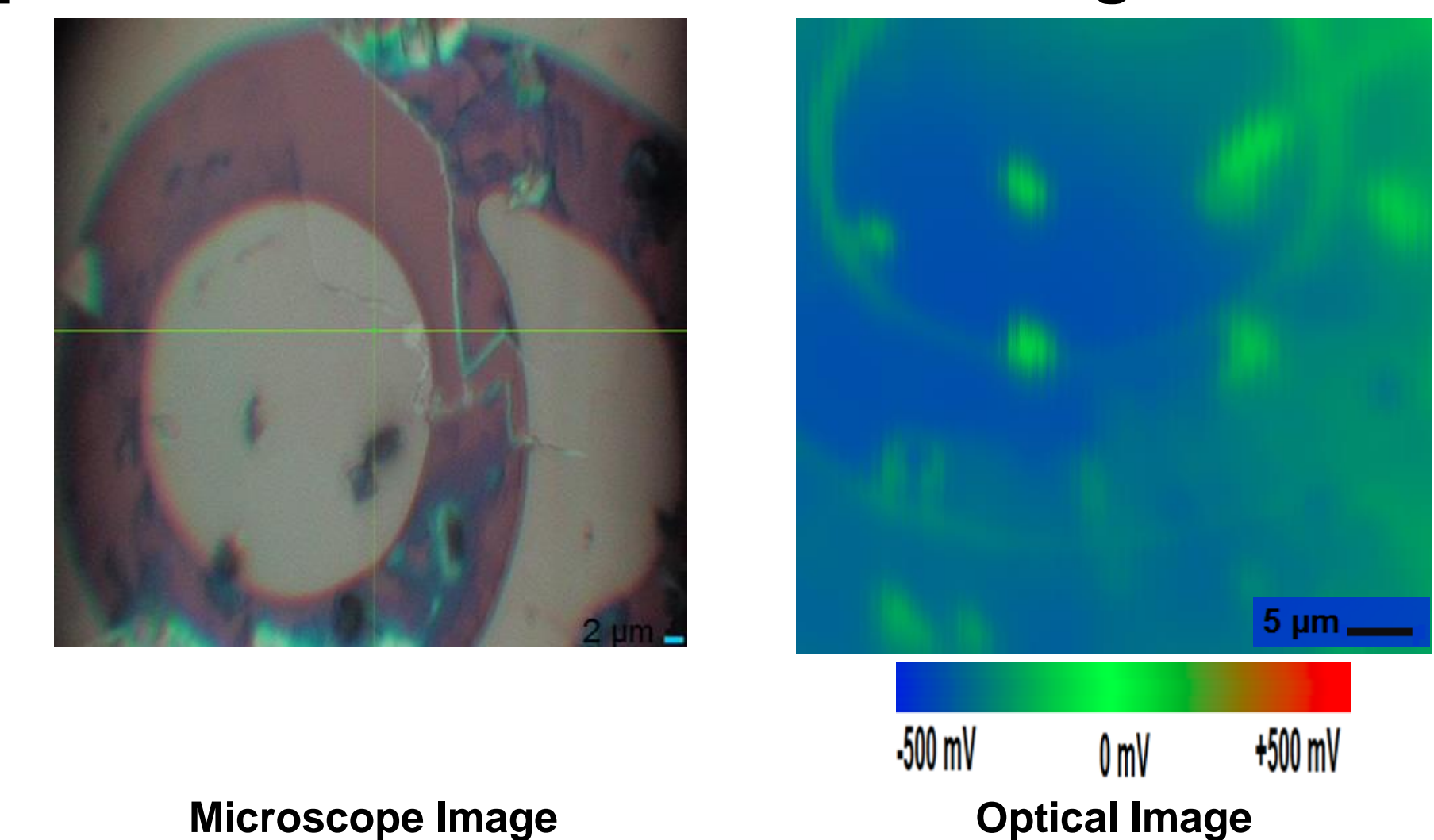


Image of photoconductive antenna is distinguishable



Optical image can discern outline of number

- However, cannot detect monolayer Raman spectroscopy-confirmed MoS₂ (D₂₀) on “9”
- Resolution is not good enough for terahertz imaging

Conclusions and Future Work

Finer tuning will be required to achieve higher quality optical images and terahertz images

- Currently resolution is ~5 μ m
- Resolution up to ~1 μ m achievable

Delay the deterioration of p-n junction

- Determine the thickness of resultant bulk MoS₂ layers
- Understand why oxidation of silicon results in conglomeration of MoS₂

Reference

¹ Bo Li et al., in preparation

Acknowledgments

This research project was conducted as part of the 2015 NanoJapan: International Research Experience for Undergraduates Program with support from a National Science Foundation Partnerships for International Research & Education grant (NSF-PIRE OISE-0968405). For more information on NanoJapan see <http://nanojapan.rice.edu>. Further inquiries can be directed to wongrebe17@grinnell.edu